



US005347854A

United States Patent [19]

Martin et al.

[11] Patent Number: 5,347,854

[45] Date of Patent: Sep. 20, 1994

[54] TWO DIMENSIONAL PROFILING WITH A
CONTACT FORCE ATOMIC FORCE
MICROSCOPE

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[21] Appl. No.: 948,503

[22] Filed: Sep. 22, 1992

[51] Int. Cl.⁵ G01B 5/28

[52] U.S. Cl. 73/105

[58] Field of Search 73/105; 250/306, 307;
33/558-561

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[57] ABSTRACT

Two dimensional profiling of samples, such as integrated circuits containing trenches or lines, is accomplished using contact force atomic force microscopy by controlling the tip position responsive to the real-time measured local slope of the surface in contact with the tip.

5 Claims, 4 Drawing Sheets

